

## 參考文獻

1. <http://nano.nchc.org.tw/>
2. E. Yablonovitch ,Inhibited Spontaneous Emission in Solid-State Physics and Electronics, Physical Review Letters , 18 May 1987
3. S. John ,Strong Localization of Photons in Certain Disordered Dielectric Superlattices , Physical Review Letters , 8 June 1987 .
4. Dongmin Wu, Nicholas Fang, Cheng Sun, and Xiang Zhang,Therahertz plasmonic high pass filter., APPLIED PHYSICS LETTERS VOLUME 83, NUMBER 17 JULY 2003
5. A.G. Peele,T. H. K. Irving,K. A. Nugent,D. C. Mancini, N. Moldovan,T. R. Christenson,Production issues for high aspect ratio Lobster-eye optics using LIGA,J. Microsyst. Technol., 9, 55-60 (2002)
6. 許博淵, X-ray Micromachining 上課講義,3 月, 2003
7. A. L. Bogdanov and S. S. Peredkov, Microelectronic Eng. 53(2000) P.493-496
8. 劉昆沛, 高感度 SU-8 光阻之超深 X 光光刻技術研究,交通大學機械研究所碩士論文,2003
9. 曾賢德,光子晶體(Photonic Crystal)
10. Ying Xu et.al., J. Opt. Soc. Am. **18**, 1084 , 2001
11. F. S.-S. Chien, C.-L. Wu, Y.-C. Chou, T. T. Chen, S. Gwo, and W.-F. Hsieh., Nanomachining of (110)-oriented silicon by scanning probe lithography and anisotropic wet etching , Appl. Phys. Lett. 75, 2429 , 1999 .

12. A. Boisen, K. Birkelund, O. Hansen, and F. Grey, *J. Vac. Sci. Technol. B* 16, 2977 (1998)
13. J. D. Joannopoulos, P. R. Villeneuve and S. Fan, *Nature* 386, 143 (1997) or J. D. Joannopoulos, R. D. Meade, and J. N. Winn, *Photonic Crystals*, Princeton, New York, 1995
14. 蔡雅芝, 淺談光子晶體, *物理雙月刊* 21, 445, 1998
15. <http://www.rpi.edu/~zhangxc>
16. 林輝慶, 兆赫波輻射的產生與偵測, 成功大學物理研究所碩士論文, 2003
17. 馮右雄, 半導體兆赫波源及電流震盪器之研究, 交通大學電子研究所碩士論文, 2003
18. Bridge for the terahertz gap, Carlo Sirtori, *Macmillan Magazines*, 2002
19. 楊啟榮, 強玲英, 黃奇聲, “微系統 LIGA 製程之精密電鑄技術”, *科儀新知*, 2(1), pp.4-16, 2000.
20. 陳炳輝, 微機電技術
21. W. Ehrfeld, P. Bley, F. Gotz, J. Mohr, D. Munchmeyer, W. Schelb, *J. Vac. Sci. Technol. B*, Vol. 6, No. 1, 178-182, 1988.
22. 蔡仁傑, 砷離子佈植砷化鎵光導天線產生次毫米波的綜合研究, 交通大學光電所碩士論文, 2000
23. Wayne M. Moreau, *Semiconductor Lithography Principles, Practices, and Materials*
24. Thomas R. Boehme, *Mechanical Properties of Nanoscopic Structures*

Using Molecular Dynamics.,Department of Chemical Engineering,  
University of Wisconsin 2001

25.G Czech, E C Richter, O Wunnicke,193nm Resists: A Status Report  
(Part One)

26.Heidi Cao,Kenji Yoshimoto,Paul Nealey,Characterization and  
Modeling of Photoresist Pattern Collapse

27.Budynas, R.G. , Advanced Strength and Applied Stress Analysis. ,  
McGraw-Hill 1977

28.G.Bleidiessel, et al., “Dependence of the quality of thick resist  
structures on resist baking” ,Microelectronic Engineering 41/42 (1998)  
pp.433-436.

